PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Takao SAITO et al.

Group Art Unit: 1762

Application No.: 10/766,806

Filed: January 30, 2004

Docket No.: 115556

For: METHOD AND SYSTEM FOR FORMING THIN FILMS

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- This Information Disclosure Statement is being filed (a) within three months of 冈 the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- The references 1-4 were cited in a counterpart foreign application. An English X language version of the foreign search report is attached for the Examiner's information.
- In accordance with 37 CFR §1.98(a)(2)(i), copies of any U.S. patents and patent 冈 3. application publications are not attached.

Respectfully submitted,

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Date: November 19, 2004

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DEPOSIT ACCOUNT USE **AUTHORIZATION** Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461

Sheet 1 of 1

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INFO	RMATI	ION DISCLOSURE STATEMENT							
(Use several sheets if necessary)				APPLICANTS Takao SAITO et al.					
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		U.S. I	ATI	ENT DOCU	MENTS				
EXAMINER INITIAL		DOCUMENT NUMBER	DATE 11/21/2002 12/5/2002 8/17/1993		NAME		CLASS	SUB CLASS	
	1.	US 2002/0170495 A1			NAKAMURA et al.				
	2.	US 2002/0182319 A1			BEN-MALEK et al.				
	3.	5,236,511			ETZKORN et al.				
									
	1	FOREIG	FOREIGN PATENT DOCUMENTS				<u> </u>	OT TO	
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		OTHER DOCUMENTS (Inc	ludi	ng Author,	Title, Date, Pertinent Pages, e	etc.)			
	4. Frank Jansen et al.; "Thin film deposition on inside surfaces by plasma enhanced chemical vapor deposition"; XP000474735; Thin Solid Films, Elsevier, Vol. 252, No. 1; November 15, 1994; pp 32-37								
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EXAMINER					DATE CONSIDERED				
Examiner:	Initial confort	if citation considered, whether or not ci	tatio	on is in coi	nformance with M.P.E.P. 60 next communication to appli	9; draw lin	e through citat	ion if not in	